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L3 ANSWER 6 OF 7 CAPLUS COPYRIGHT 2003 ACS
AN 1997:533759 CAPLUS
DN 127:141981
TI Electrodeposition solution for forming tin and tin-lead alloy
IN Kodama, Atsushi
PA Nippon Mining Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 4 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IC ICM C25D003-32
ICS C25D003-56
CC 72-8 (Electrochemistry)
Section cross-reference(s): 56

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PI	JP 09184087	A2	19970715	JP 1995-343115	19951228
PRAI	JP 1995-343115		19951228		

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AB The title aq. soln. contains an org. sulfonic acid, a Sn²⁺ salt of an org.

sulfonic acid (and optionally a Pb²⁺ salt of an org. sulfonic acid), polyoxyethylene alkylphenyl ether or polyoxyethylene naphthyl ether as a dispersing agent, and **chlorobenzaldehyde**, naphthaldehyde, and paraacetaldehyde as a brightener. A bright Sn alloy and Sn-Pb alloy can be plated at wide c.d. region.

ST tin electrodeposition bath; lead tin alloy electroplating bath

IT Electrodeposition

(electrodeposition bath for tin and tin-lead alloy)

IT 123-63-7, Paracetaldehyde 30678-61-6, Naphthaldehyde 35913-09-8,
Chlorobenzaldehyde

RL: TEM (Technical or engineered material use); USES (Uses)
(brightener; in electrodeposition bath for tin and tin-lead alloy)

IT 9016-45-9, Polyethylene oxide nonylphenyl ether 69778-08-1,
Polyethylene
oxide mononaphthyl ether

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)
(dispersing agent; in electrodeposition bath for tin and tin-lead alloy)

IT 75-75-2, Methanesulfonic acid 95860-12-1, **Lead**
methanesulfonate 95860-13-2, **Tin**

methanesulfonate
RL: TEM (Technical or engineered material use); USES (Uses)
(in electrodeposition bath for tin and tin-lead alloy)